



## Product Data Sheet

### Si for Plasma Spraying

Silicio FerroSolar offers finely ground silicon powder with different chemical compositions for the production of sputtering targets. Sputtering targets are produced by Plasma Spraying and they are used in a sputtering process for deposition of a thin film on a substrate, such as coating of glass.

#### Chemical composition

	<b>2N</b>	<b>3N</b>	<b>4N</b>
	<b>Spec.</b>	<b>Spec.</b>	<b>Spec.</b>
Si Content (%)	>99	>99.9	>99.99
<b>IMPURITIES (%):</b>			
Fe	<0.50	<0.05	<0.005
Al	<0.20	<0.01	<0.001
Ca	<0.05	<0.01	<0.001
Ti	<0.02	<0.005	<1ppmw
P*	5-20 ppmw	5-20 ppmw	5-20 ppmw
B*	25-35 ppmw	25-35 ppmw	25-35 ppmw

\*These are the typical range values for B and P. Any target value could be produced.

\*\*Other trace elements on request

#### Particle size

Sizes could be adapted to the different needs. Typical sizes are 45-90 microns.

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